Evaluation of Negative Capacitance Ferroelectric Field-Effect Transistors For Low Power Circuit Applications

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Abstract - Both digital and analog circuit performance of negative capacitance ferroelectric field-effect transistor (NC-FET) is evaluated based on its equivalent circuit model. HfZrO₂ is used as the ferroelectric with a reported damping constant ξ_{FE} of 10 Ω ·m. Due to internal voltage amplification, both supply voltage V_{DD} and subthreshold swing of NC-FET are reduced as compared with the control. This could enable the employment of NC-FET in lowpower and high-frequency digital circuits if ξ_{FE} is less than $10^{-2} \Omega$ ·m. In addition, NC-FET has I_{DS} - V_{DS} characteristic with a smaller output resistance at linear region and a larger resistance at saturation region, as compared with MOSFET. Therefore, NC-FET is beneficial in analog design such as lower on resistance in analog switch and more precise current transfer in the current mirror.

1. Introduction

Negative capacitance ferroelectric field-effect transistor (NC-FET) is a potential low power device with sub-60 mV/decade subthreshold swing (SS) [Fig. 1(a)] [1-15]. Most of the previous results confirmed the reduction of its supply voltage $V_{\rm DD}$ and subthreshold swing (SS) to suppress the rapidly increasing power density in digital circuits. However, its analog circuit performance is seldom discussed. In this work, a comprehensive evaluation on both digital and analog performance of NC-FET is provided.

2. Simulation Method

The dimensions of n- and p-channel devices (W_G/L_G) are 50 nm/50 nm and 100 nm/50 nm, respectively. 45 nm metal gate/high-*k* CMOS is used as the bottom structure and its electrical characteristics are predicted by BSIM4 in HSPICE. HfZrO₂ is used as the ferroelectric with Landau parameters $\alpha_{\text{FE}} = -8.5 \times 10^8 \text{ m/F}$ and $\beta_{\text{FE}} = 1.8 \times 10^9 \text{ m}^5/\text{F/C}^2$ and damping constant $\xi_{\text{FE}} = 10 \ \Omega$ ·m. According to Landau-Khalatnikov equation (1), its equivalent circuit model is a series connection of a voltage controlled voltage source (VCVS) $V_{\text{FE,S}}$ and a resistor R_{FE} [Fig. 1(b)] [16, 17]. Here, t_{FE} is the ferroelectric thickness and V_{FE} is the voltage drop across it.

$$\xi_{FE}t_{FE}\frac{dP}{dt} + 2\alpha_{FE}t_{FE}P + 4\beta_{FE}t_{FE}P^3 = V_{FE} \cdot$$
(1)

3. Results and Discussion

Due to internal voltage amplification, a steeper swing in NC-FET is achieved [Fig. 2(a)]. Both V_{DD} (for $I_{on} = 1.4$ mA/µm) and threshold voltage V_T ($I_T = 10$ µA/µm) are reduced [Fig. 2(b)]. SS can be lower than 60 mV/decade when t_{FE} is larger than 20 nm [Fig. 2(c)].

For its output characteristics, a negative differential resistance (NDR) is observed when V_{GS} is 0.2 V [Fig. 3(a)]. This is attributed to $Q_{\rm G}$ modulation by $V_{\rm DS}$. For $V_{\rm GS} = 0.5$ V and 0.8 V, the output resistance $R_{\rm OUT}$ of NC-FET is smaller at linear region and larger at saturation region [Figs. 3(b) and 3(c)]. This feature is beneficial for analog design.

A three-stage inverter chain is used for circuit-level evaluation [Fig. 4(a)]. For a fair comparison with the same on/offstate currents, V_{DD} is set at 1.0 V and 0.71 V for MOSFET and NC-FET inverter chain, respectively. When ζ_{FE} is 10 Ω ·m, the average propagation delay is 2.83 ns [Fig. 4(b)]. The dependence of delay on ζ_{FE} in Fig. 4(c) clearly shows that ζ_{FE} should be lower than 10⁻² Ω ·m for high frequency use.

Power evaluation in Fig. 5(a) demonstrates that, for $\xi_{FE} = 10 \Omega \cdot m$, short circuit power is dominant since an identical current flows through both NC-FETs. However, if ξ_{FE} can be lower than $10^{-2} \Omega \cdot m$, either NC-FET is switched off so that short circuit power is eliminated and switching power consumes most energy [Fig. 5(b)]. Dependence of energy consumption on ξ_{FE} in Fig. 5(c) shows that NC-FET could be a lower power device than MOSFET for $\xi_{FE} < 10^{-2} \Omega \cdot m$.

The lower R_{OUT} of NC-FET at linear region can be used in analog switch to provide smaller on-state resistance (Fig. 6). While the larger R_{OUT} at saturation region can be used in current mirror for more precise current transfer (Fig. 7).

4. Conclusions

NC-FET could achieve steeper swing than MOSFET. $\xi_{\text{FE}} \leq 10^{-2} \,\Omega$ ·m is required for the NC-FET to be used in low-power high-frequency digital circuits. The small R_{OUT} at linear region and larger R_{OUT} at saturation region could enable potential applications of NC-FET in analog circuits.

Acknowledgements

The authors gratefully acknowledge the support by the Ministry of Education of Singapore under Grant No. MOE2017-T2-1-114 and R-263-000-C58-133.

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Fig. 2. (a) Steeper I_{DS} - V_{GS} characteristics of NC-FET with larger t_{FE} . (b) V_{DD} and V_T reduction with larger t_{FE} . (c) SS can be reduced to 48 mV/decade if t_{FE} is 30 nm.



Fig. 1. (a) NC-FET structure. (b) Equivalent circuit model of ferroelectric (FE) consists of VCVS and R_{FE} .

Fig. 3. Comparison of I_{DS} - V_{DS} characteristics between NC-FET (red) and MOSFET (black) at (a) $V_{GS} = 0.2$ V, (b) 0.5 V, and (c) 0.8 V. NDR is observed when V_{GS} is 0.2 V.



Fig. 4. (a) A three-stage inverter chain is used for digital evaluation. (b) Propagation characteristic shows that the average delay of each stage is 2.83 ns. (c) Dependence of delay on ξ_{FE} shows that $\xi_{\text{FE}} < 10^{-2} \,\Omega$ ·m is required to achieve the similar delay to MOSFET.



Fig.5. (a) The simultaneous power consumption of NC-FETs in the 1st stage indicates that short circuit power is dominant for $\xi_{FE} = 10$ Ω ·m. (b) For $\xi_{FE} = 10^{-3} \Omega$ ·m, either NC-FET consumes energy during switching indicates that the dominant power is switching power $C_L V_{DD}^2$. (c) Dependence of energy consumption per cycle on ξ_{FE} shows that $\xi_{FE} \le 10^{-2} \Omega$ ·m is required for low power circuit applications.





Fig. 6. Analog switch consisting of NC-FETs exhibits lower on resistance R_{ON} for both $V_{DD} = 1.0$ V in (a) and 0.5 V in (b).

Fig. 7. Current mirror comprised by NC-FETs can transfer I_{SS} to I_{OUT} more precisely for a wide range.

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